

EXAMINER'S AMENDMENT

1. The amendment after final filed August 27, 2008 has been entered.
2. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Mr. Rowe on 4/20/2009.

The application has been amended as follows:

Claims 1-3: (Cancelled)

Claim 4 (Currently amended): A method for producing a powder represented by the formula ~~SiO_x~~ SiO_x comprising:

reacting monosilane gas, SiH₄, with a gas containing oxygen capable of oxidizing the monosilane gas ~~in a non-oxidizing atmosphere~~ in the presence of a non-oxidizing gas, under a pressure of from 10 to 1000 kPa at a high temperature of from 500 to 1000°C in a reaction zone to produce SiO_x powder,

wherein

x is from 0.6 to 1.8,

the SiO_x powder has a specific surface area of at least 10 m²/g and a total content of Na, Fe, Al and Cl of at most 10 ppm, and

~~in the reacting,~~

the gas capable of oxidizing the monosilane gas is supplied to a ~~high temperature part of a reactor~~ the reaction zone without prior mixing with the monosilane gas, and the ~~high temperature of 500 to 1000°C in the reaction zone~~ is obtained by heating the ~~reactor~~ reaction zone on its periphery.

Claim 5 (Currently Amended): The method according to Claim 4, wherein ~~the content in molar ratio of~~ on a molar basis, the non-oxidizing gas is at least twice the total amount of the monosilane gas and oxygen ~~participating in the oxidation of~~ contained in the gas capable of oxidizing the monosilane gas.

Claim 6 (Previously presented): The method according to Claim 4, wherein the gas capable of oxidizing the monosilane gas is oxygen, air, NO₂, CO₂, or H₂O.

Claim 7 (Previously presented): The method according to Claim 4, wherein the non-oxidizing gas is argon or helium.

Claim 8 (Previously presented): The method according to Claim 4, wherein the pressure is from 50 to 300 kPa and the temperature is from 500 to 1000°C.

Claim 9: (Cancelled)

Claim 10 (Currently amended): The method according to Claim 4, wherein the ~~reactor~~ reaction zone and gas introduction pipes are made of quartz.

Claim 11 (Previously presented): The method according to Claim 4, wherein the value of x in the formula SiO_x is produced by changing the proportion of the monosilane gas to the oxidizing gas.

Claim 12 (Previously presented): The method according to Claim 4, wherein the SiO_x powder is recovered by a powder recovery apparatus.

Claim 13 (Currently amended): The method according to Claim 4, wherein the residual time of the monosilane gas and oxidizing gas in the ~~reactor~~ reaction zone is from 0.2 to 1 second.

Claim 14 (Previously presented): The method according to Claim 4, wherein the reacting is at a temperature of 550 to 950°C.

Claim 15 (Previously presented): The method according to Claim 4, wherein the reacting is at a temperature of 650 to 850°C.

3. The following is an examiner's statement of reasons for allowance: The prior art does not teach or suggest the oxidation of monosilane (SiH_4) to create a silicon suboxide power at the claimed temperature. The closest prior art does not use SiH_4 as the silicon source. Prior art using SiH_4 as a source are not processes to create SiO_x .

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to DIANA J. LIAO whose telephone number is (571)270-3592. The examiner can normally be reached on Monday - Friday 8:00am to 5:30pm EST.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Stanley Silverman can be reached on 571-272-1358. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

/Ngoc-Yen M. Nguyen/
Primary Examiner, Art Unit 1793

DJL